

## United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/686,893	10/16/2003	Hidetoshi Ishida	YAO-3990US3	8582
23122	7590 08/31/2005		EXAMINER	
RATNERPRESTIA			JEFFERSON, QUOVAUNDA	
P O BOX 980 VALLEY FORGE, PA 19482-0980			ART UNIT	PAPER NUMBER
,	,		2823	
			DATE MAILED: 08/31/2005	5

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)			
	10/686,893	ISHIDA ET AL.			
Office Action Summary	Examiner	Art Unit			
	Quovaunda Jefferson	2823			
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply					
A SHORTENED STATUTORY PERIOD FOR REPL' THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a repl - If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statute - Any reply received by the Office later than three months after the mailing - earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be time y within the statutory minimum of thirty (30) days will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE.	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).			
Status					
1) Responsive to communication(s) filed on 16 C	October 2003.				
2a) This action is <b>FINAL</b> . 2b) ☑ This	This action is <b>FINAL</b> . 2b)⊠ This action is non-final.				
·	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.				
Disposition of Claims	·				
4) ⊠ Claim(s) <u>8-11</u> is/are pending in the application 4a) Of the above claim(s) is/are withdra  5) □ Claim(s) is/are allowed.  6) ⊠ Claim(s) <u>8-11</u> is/are rejected.  7) □ Claim(s) is/are objected to.  8) □ Claim(s) are subject to restriction and/or	wn from consideration.				
Application Papers					
9) The specification is objected to by the Examiner.					
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.					
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).					
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).  11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.					
Priority under 35 U.S.C. § 119					
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of:  1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Burea * See the attached detailed Office action for a list	ts have been received. ts have been received in Applicati ority documents have been receive u (PCT Rule 17.2(a)).	on No ed in this National Stage			
Attachment(s)		• •			
1) Notice of References Cited (PTO-892)  4) Interview Summary (PTO-413)					
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	Paper No(s)/Mail D				

Application/Control Number: 10/686,893

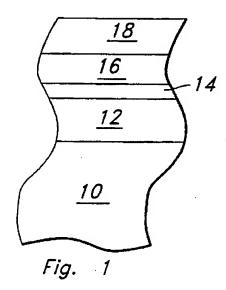
Art Unit: 2823

## **DETAILED ACTION**

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.



Claims 8-11 are rejected under 35 U.S.C. 103(a) as being unpatentable over <u>Summerfelt</u> et al, US Patent 5,326,721. See figure 1 above.

Pertaining to claims 8-11, <u>Summerfelt</u> teaches a semiconductor device having a titanium material layer **16** and a silicon oxide layer **12** wherein the titanium material layer includes at least one material selected from the group consisting of BaTi0<sub>3</sub>, SrTi0<sub>3</sub>, Ba<sub>x</sub>Sr<sub>(1-x)</sub>, Ti0<sub>3</sub>, and similar Group IIA metal titanates.

Application/Control Number: 10/686,893

Art Unit: 2823

However, <u>Summerfelt</u> fails teach the following:

A semiconductor device having a titanium material layer and a silicon oxide layer produced by a process including the step of etching at least one of the titanium material layer and the silicon oxide layer using an etchant, wherein the etchant includes a mixed liquid of HCI, NH<sub>4</sub>F and H<sub>2</sub>O; and setting a molar ratio of NH<sub>4</sub>F/HCI in the mixed liquid, the molar ratio being set based on which of the at least one of the titanium material layer and the silicon oxide layer is to be etched;

The semiconductor device having a titanium material layer and a silicon oxide layer produced by a process, wherein the step of setting a molar ratio of NH4F/HCI includes setting the molar ratio of NH4F/HCI to less than 1 in the case where the titanium material layer is to be etched;

The semiconductor device produced by a process wherein the step of setting a molar ratio of NH4F/HCI includes setting the molar ratio of NH4F/HCI to less than 1 in the case where the silicon oxide layer is to be etched;

The semiconductor device produced by a process wherein the step of setting a molar ratio of NH4F/HCl includes setting the molar ratio of NH4F/HCl in the range from about 0.8 to about 1.2 in the case where both the titanium material layer and the silicon oxide layer are to be etched.

According to the MPEP, Section 2113, "Even though product-by-process claims are limited by and defined by the process, determination of patentability is based on the product itself, the patentability of a product does not depend on its method of production. If the product in the product-by-process claim is the same as or obvious from a product of the prior art, the claim is unpatentable even though the prior product was made by a different process".

In re Thorpe, 777 F.2d 695, 698, 227 USPQ 964, 966 (Fed. Cir. 1985) (citations omitted) (Claim was directed to a novolac color developer. The process of making the developer was allowed. The difference between the inventive process and the prior art was the addition of metal oxide and carboxylic acid as separate ingredients instead of adding the more expensive pre-reacted metal carboxylate. The product-by-process claim was rejected because the end product, in both the prior art and the allowed process, ends up containing metal carboxylate. The fact

Art Unit: 2823

that the metal carboxylate is not directly added, but is instead produced in-situ does not change the end product.).

## Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Quovaunda Jefferson whose telephone number is 571-272-5051. The examiner can normally be reached on Monday through Friday, 8AM to 4:30PM EST.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Matthew Smith can be reached on 571-272-1907. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

qvj

W. DAVID COLEMAN PRIMARY EXAMINER